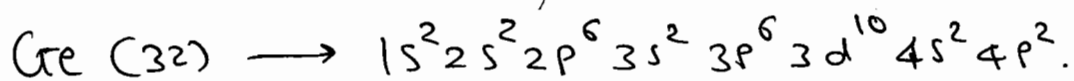
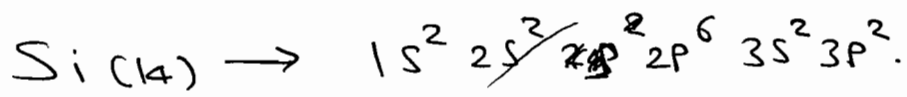
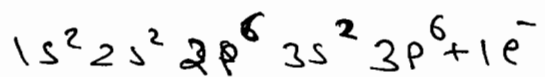
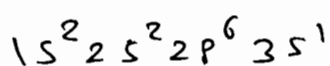
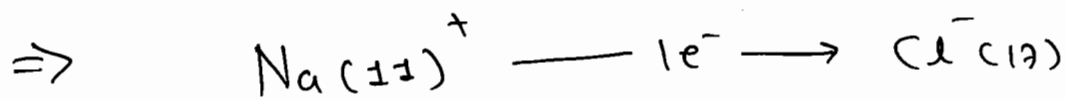


☆ Intrinsic (or) Pure Semiconductors:

→ Most of the electronic devices are made up of either silicon (Si) (or) Germanium (Ge) with the following Configuration:



⇒ If two silicon atoms 1 & 2 are brought very close to each other then atom-1 expects valance shell $4e^-$ of atom-2 to be given atom-1. so that incoming $4e^-$ and existing $4e^-$ make atom-1 to have $8e^-$ in valance shell. thus gets Saturation and stability.



→ If Sodium and chlorine atom are brought close to each other then Sodium will give away $3s^1$ electrons to chlorine become $+ve$ ion and gets stability with $8e^-$ in valance shell.

(2nd orbit). Chlorine by accepting 1 electron becomes -ve ion and gets stability with 8e⁻ in valance shell (3rd orbit). These two ions attract each other and ionic bond forms.

→ Chlorine gets stability by losing 1e⁻ (or) by gaining 7e⁻. Hence, losing versus gaining ratio is 1:7.

→ Silicon atom can get stability by losing 4e⁻ (or) by gaining 4e⁻. Hence losing versus gaining ratio is 4:4 (or) 1:1. In the case of sodium and chlorine since ratio is non-uniform exchange will occur. In the case of silicon since ratio is uniform sharing of electron will occur. After sharing gets completed a 3-D crystal lattice gets created.

⇒ Fig. (1) shows a 2-D view of crystal lattice of silicon.

⇒

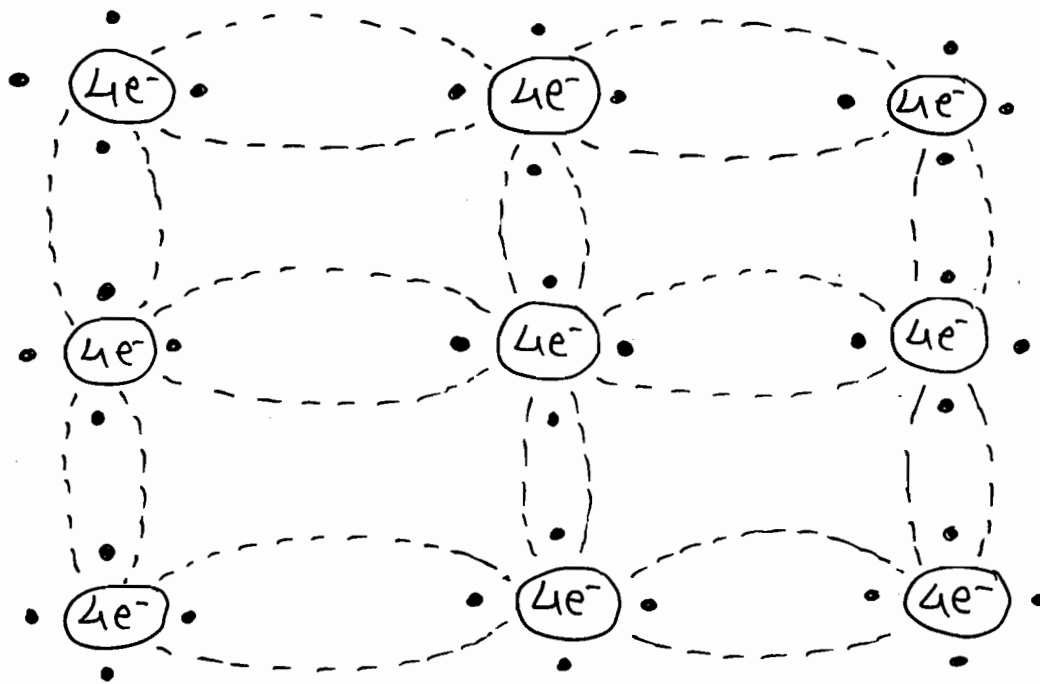


Fig-① Crystal lattice

⇒ Fig-② Shows normal atomic model of Silicon atom.

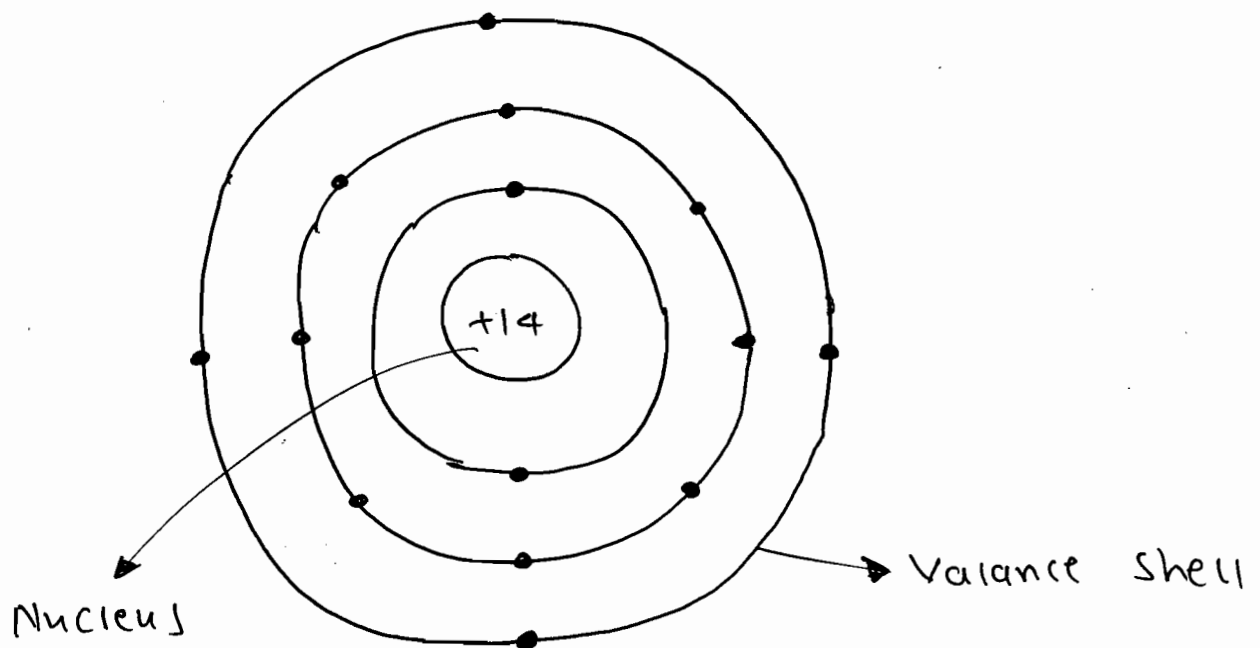


Fig-② - Atomic model of silicon atom.

⇒ All atoms are electrically neutral.

(No. of Proton = no. of Electron).

⇒ If a charge carrier moves through a

unit cross sectional area then per unit it can produce current i.e.

$$I = \frac{dq}{dt}$$

⇒ All the -vely charge electron bound to +vely charge nucleus. Such bound are immobile electron can not support current.

⇒ If an external force is applied to electron more than electric force applied by nucleus then electron comes out of force of attraction of nucleus becomes free. Such free electrons are mobile electron can support current.

⇒ As we move from the nucleus force of attraction decreases. hence to comment on conductivity only valance shell electrons only to be considered as they can made free easily.

⇒ FIG - ③ Shows modified atomic model representation of silicon atom.

⇒

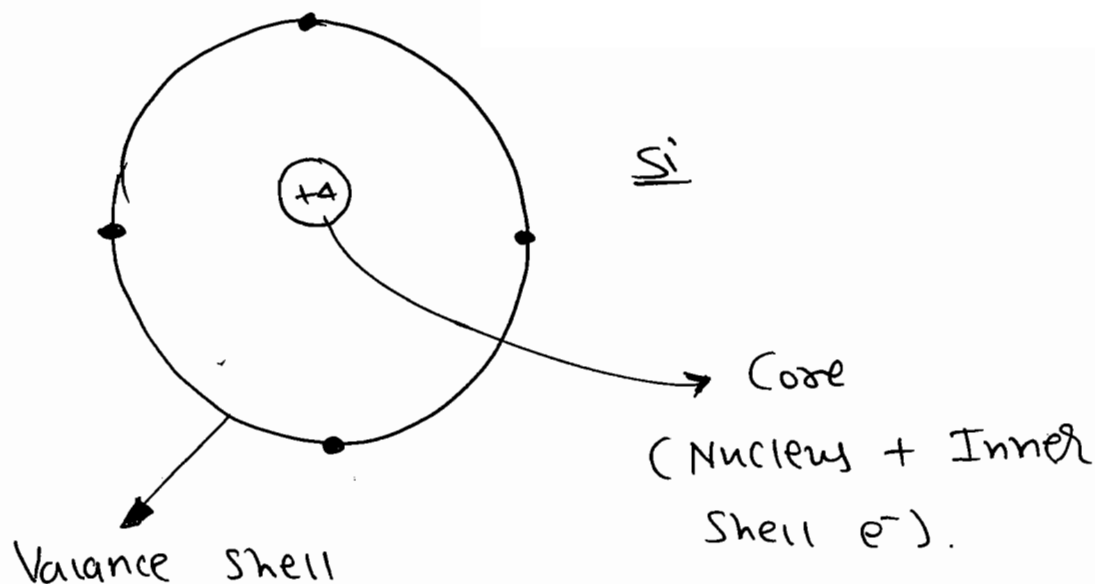


Fig-3 - Modified atomic model of Si.

→ Fig-③ is valid representation to comment on Conductivity of Silicon (or) Germanium (or) any atom of group 4 of periodic table. Using this a set of 5 atoms (or) Superimpose as in fig-④.

⇒

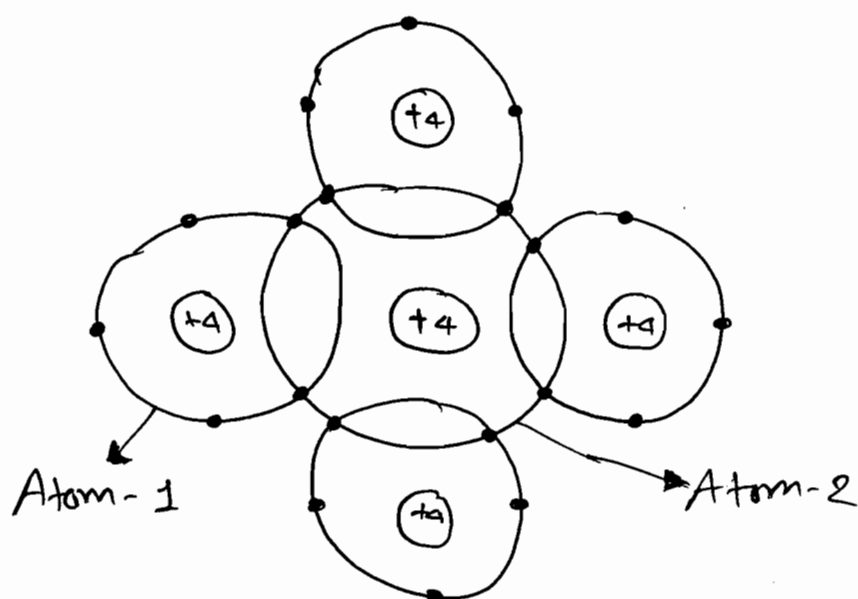


Fig-4

* Energy Band Diagram:

⇒ Collection of closely spaced discrete energy level is called energy band diagram.

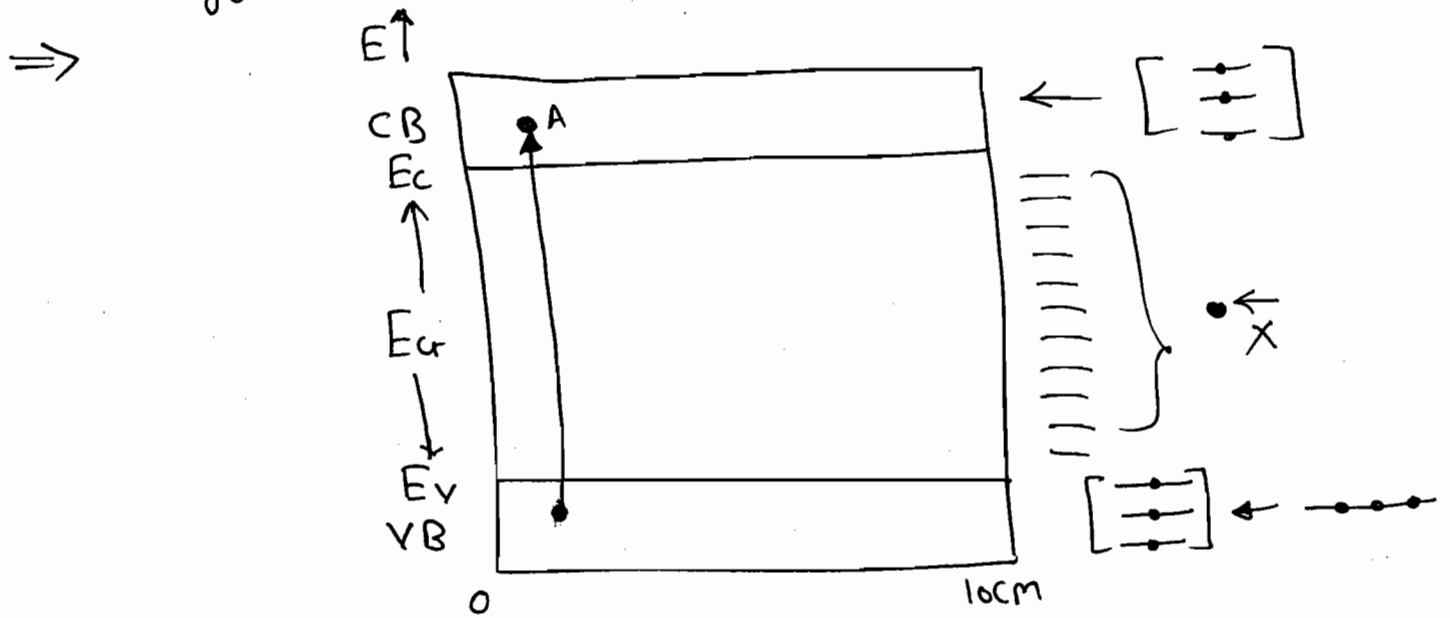


Fig- 5 - Energy Band diagram.

⇒ If all the atoms of a crystal are pulled separately and kept at larger distance from each other then all the atoms valance shell electrons will occupy the same energy level.

⇒ If atoms are brought very close to each other to form a crystal then so many electrons sitting at the same energy violates Pauli's exclusion principle which states that no two electrons belonging to the same interacting

System can have the same value for the quantum numbers n, l, m & s .

⇒ To satisfy Pauli's principle electron diverges and form valance Band (V_B).

An electron in V_B (lower energy level) belongs to valance shell and it is bound hence can not support current.

⇒ If an external energy is applied to an e^- more than the ~~exeric~~ energy with which the nucleus pulls the electron, the electrons becomes free and gets excited move to higher energy and found conduction band (CB). an electrons in CB (higher energy level) is of ~~free~~ type free and can support the current.

⇒ E_c : Lowest Energy Level (or)
Edged of Conduction band.

⇒ E_v : Highest Energy Level (or)
Edged of Valanced band.

⇒ Between E_c & E_v , energy level exist but in them electrons do not exist and it is called forbidden band (or) Energy band gap. i.e. E_g

⇒ $E_{g(ey)} = E_c - E_v$

⇒ As E_g increases material becomes insulator, As E_g decreases material becomes Conductor.

⇒ E_g approximately zero for Conductor.

⇒ At 0°K, all valance shell electrons are bound in covalent bond (i.e. bound to parent nuclei). Hence, material acts as insulator.

⇒ Covalent bonds are free, existing but not visible. Hence shown by dotted line.

⇒ At 300°K, an electron breaks a covalent bond (i.e. comes out of force of attraction of nucleus) becomes free and can be drifted to produce electron drift current in and ^{make} material Conductor.

* <u>e^- Current (I_n)</u>	<u>Hole current (I_p)</u>
① A free electron is moving.	① An electron is moving from one bound state to other.
② An electron is moving in conduction band.	② An electron is moving in valance band.
③ An electron is moving at higher energy level.	③ An electron is moving at higher lower energy level.
④ An electron is moving through interatomic gap.	④ An electron is moving from one covalent bond to other.

⇒ Non-existence of electron in a covalent bond is defined as space.

⇒ To understand, the current given by space a set of 8 atoms (or) superimpose as shown in fig-6.

⇒ Using atomic model representation of fig-③, ABCDE are covalent bonds. Each dots is a valance shell electrons sitting in a covalent bond.

⇒ Fig-⑥ is atomic model representation of crystal lattice at o.k.

⇒

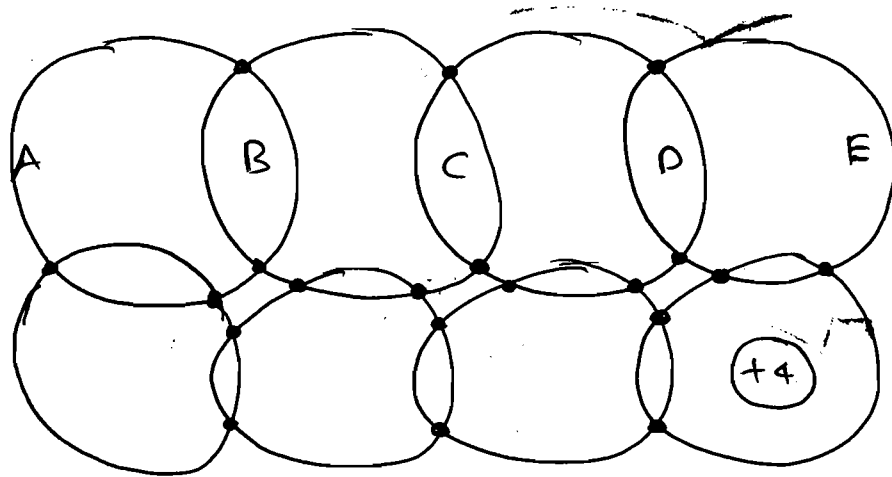


Fig - 6

⇒ At 300K an electron breaks a covalent bond becomes free and creates space as shown in fig-7.

⇒

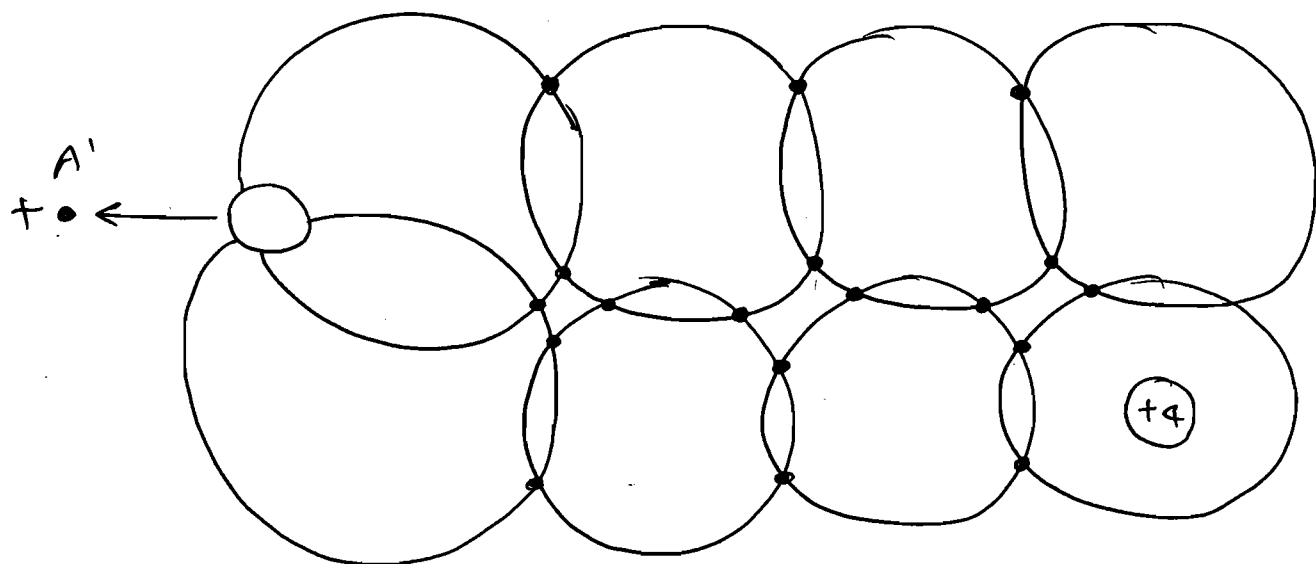


Fig - 7

→ An electron is drifting from E to A (Right to left) through EDCBA path. from EDCBA and producing current to right side as in Fig-8.

⇒

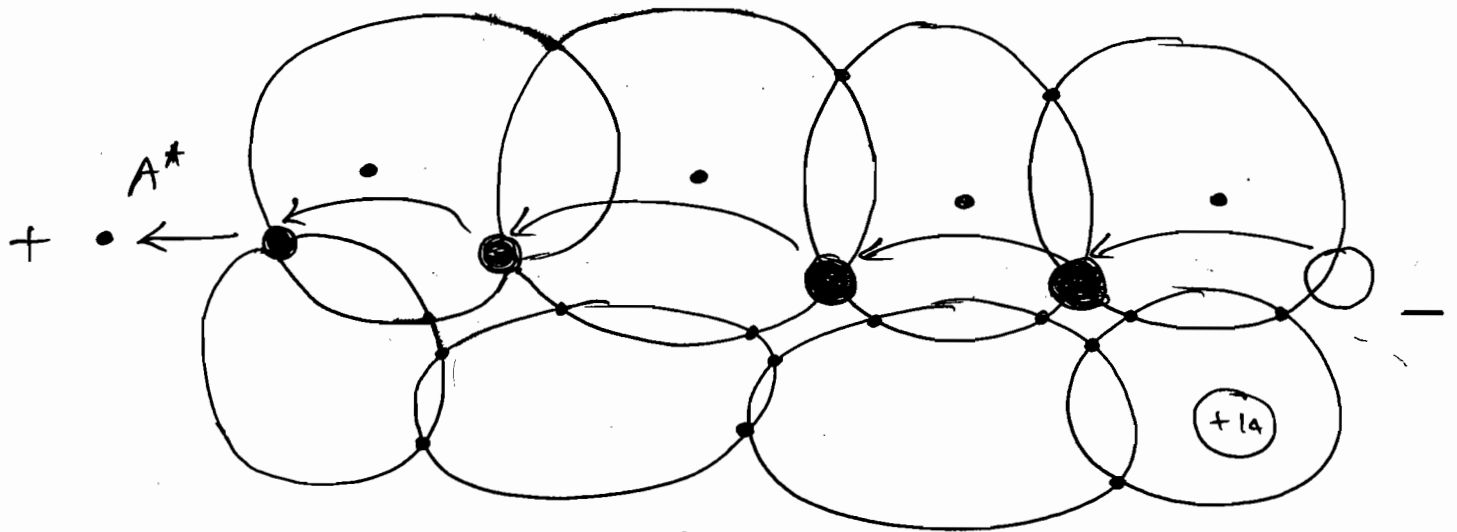


Fig- 8

⇒ The electron transition shown in atomic model of fig-8 are transfer to energy diagram as in fig-9.

⇒

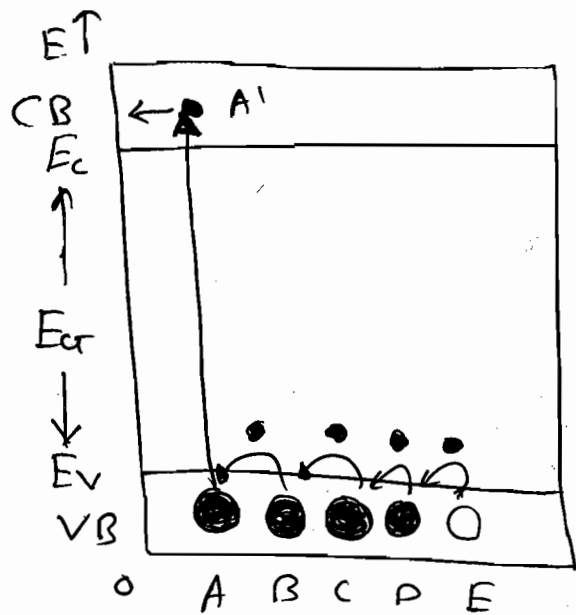


Fig- 9

⇒ Space motion from A to E through $ABCDE$ path is producing current to right side. Hence space is defined as a truly charged mobile particle called Hole.

$\Rightarrow$ If one electron goes to conduction band it leaves one hole in valance band hence called electron-hole pair (EHP) generation.

$\Rightarrow$ In n - intrinsic conduction,

$\Rightarrow$ Free electron Concentration $n =$ Hole concentration p

$\Rightarrow$ But electron current $I_n > I_p$ because

mobility of electron μ_n is greater than

mobility of hole μ_p (i.e. $\mu_n > \mu_p$) and

net current is sum of electron and hole currents.

i.e. $I = I_n + I_p$

$\Rightarrow$ Drift current,

$$I = \underbrace{nq\mu_n EA}_{I_n} + \underbrace{pq\mu_p EA}_{I_p}$$

$$\therefore I = I_n + I_p$$

$$\therefore I = nqEA [\mu_n + \mu_p]$$

⇒ Electrons and holes are moving opposite direction but current given by them will be in the same direction.

Note:

→ For IES exam (or) Engineering college teaching don't use fig - ③, ④, ⑤, ⑧.

☆ Extrinsic (or) Impure Semiconductors:

$$\Rightarrow V = nq\ell m + p q \ell p.$$

$$R = \left[\frac{L}{\sigma A} \right].$$

$$I = V/R.$$

⇒ α INT : 1mA (300°K) $\longrightarrow$ 10mA (400°K) 123°C .

✓ INT : Impurities $\longrightarrow$ EXT.

1mA : $\longleftarrow 300^\circ\text{K}$: $\longrightarrow 10\text{mA}$.

⇒ Without extrinsic semiconductor it is not possible to produce required current at room temp. and it is not possible to design an electronic device.

* Extrinsic Negative type (or)

Extrinsic n-Type Semiconductor

⇒ Pentavalent impurities (Fig-2) like Phosphorus, Arsenic, Antimony (or) Bismuth are added to an intrinsic semiconductor.

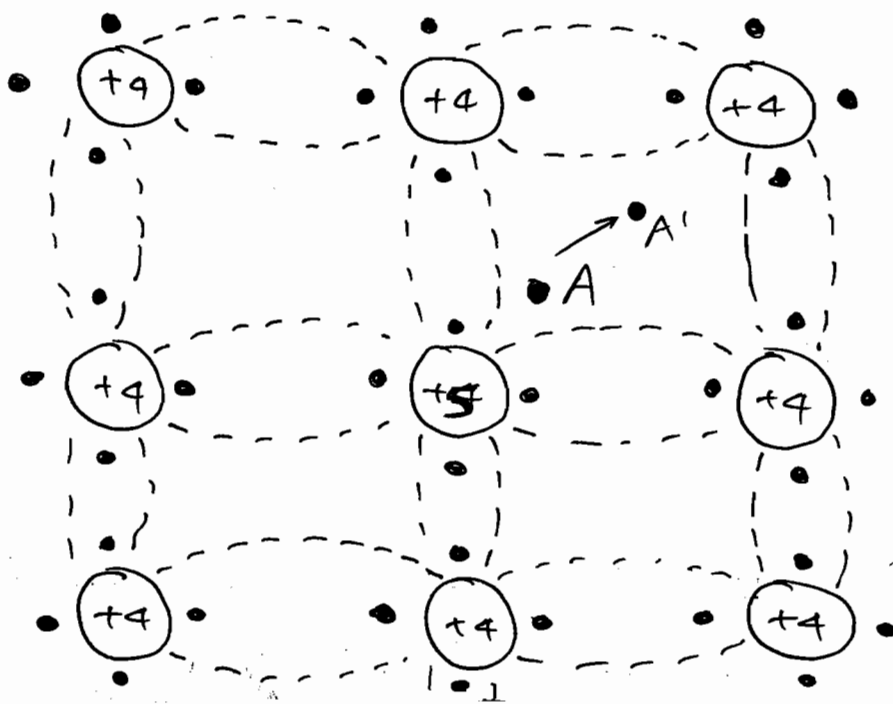
⇒ When a pentavalent atom replaces a tetravalent silicon (or) Germanium atom then out of five valance electron four electrons are supplied to four covalent bonds and one electron is excess as in crystal lattice (Fig-1).

⇒ All such excess electron occupy a new energy level E_d at 0°K slightly below conduction band at 0.01 eV for Germanium and 0.05 eV for silicon as in energy diagram (Fig-3).

⇒

Fig-1

Fig-



⇒

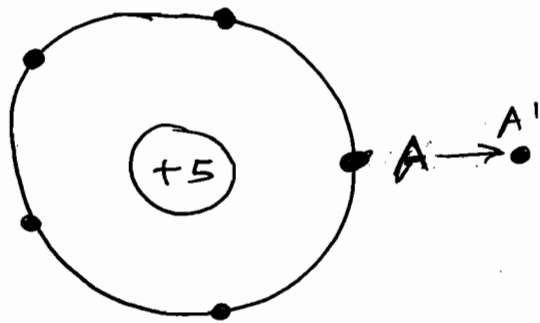


FIG - 2

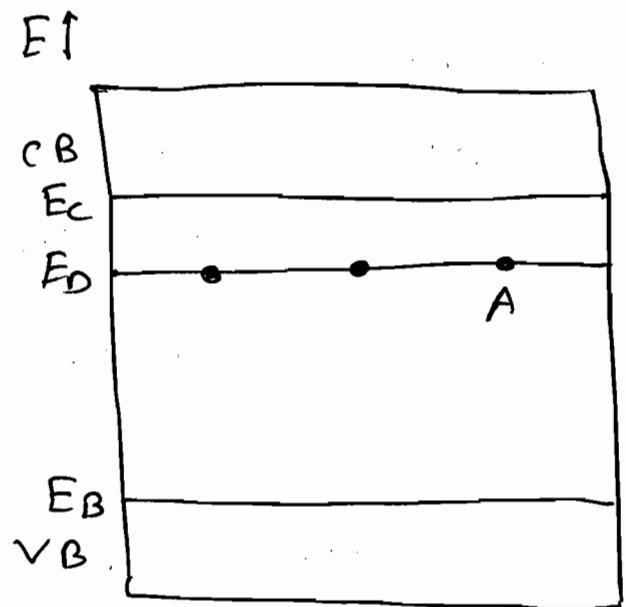


FIG - ③

⇒ At 0°K all intrinsic and extrinsic Semiconductors act as insulators.

⇒ At 0°K from Fig-3, $n=0$ & $p=0$
hence $\sigma=0$, $R=\infty$ & $I=0$. i.e. Insulator.

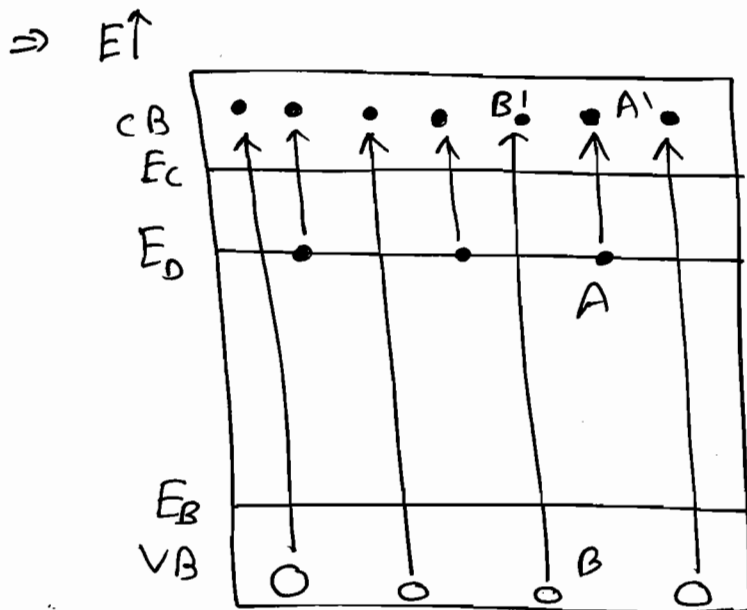


FIG - 4

⇒ At 50°K for Ge and 100°K for silicon Pentavalent impurities loose excess electrons

becomes +ve ion called impurity ionization (I.I). Hence $n > 0$ and $p \approx 0$. Hence, $\sigma > 0$, $R < \infty$ and $I > 0$ i.e. conductor.

$\Rightarrow$ Pentavalent atom is giving $1 e^-$ for support of current hence called donor atom.

$\Rightarrow E_D$: donor energy level.

$\Rightarrow$ At $300^\circ K$ electron hole pair (EHP) generation (or) Band to Band (B.B) transition occurs. Hence, n increases and p increases. Hence, σ increases, R decreases and I increases. i.e. more current is possible in extrinsic than intrinsic due to I.I. (Impurity Ionization)

$$I = I_n(I.I) + I_n(B.B) + I_p(B.B) = I_n + I_p$$

$\rightarrow I_n(I.I)$: Current due to I_n electrons given by I.I.

$\rightarrow I_n(B.B)$: Current due to electrons given by B.B

$\rightarrow I_p(B.B)$: Current due to holes given by B.B

⇒ Lightly bond electron becoming free
can not create hole. A hole is
created when electron breaks a
covalent bonds.

⇒ To Comment on the type of semiconductor
never compare currents always compare
concentration i.e.

$n = p$	→	INT.
$n \neq p$	→	EXT.
$n > p$	→	N-TYPE.
$n < p$	→	P-TYPE.

⇒ All intrinsic and extrinsic semiconductor
✓ are electrically neutral.

⇒ Charge carriers which are more in no.
or are called majority carriers and
current given by them is called
majority current i.e.

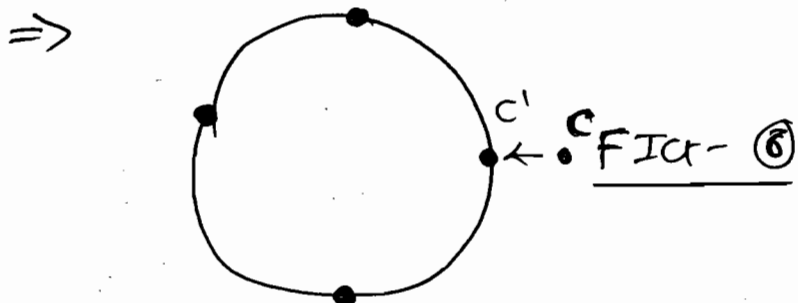
Majority Carriers	→	e^-
minority Carriers	→	Hole
Majority Currents	→	I_n
Minority Currents	→	I_p

⇒ Negatively Charge electrons are majority Carriers. Hence, called extrinsic negative type Semiconductor.

* Extrinsic Positive type (or) Extrinsic P-type (or) P-type Semiconductor:

⇒ Trivalent impurities (Fig-6) like Boron, Aluminium, Gallium (or) Indium are added to an intrinsic semiconductor.

⇒ When a trivalent atom replaces a tetravalent silicon (or) Ge atom then to form covalent bond only 3 valence e^- are supplied hence one excess hole created as in crystal lattice (Fig-5). All such excess holes occupy a new energy level E_A at 0°K above valence band at 0.01 eV for Ge and 0.05 eV for Si. as shown in Energy diagram (Fig-7).



⇒

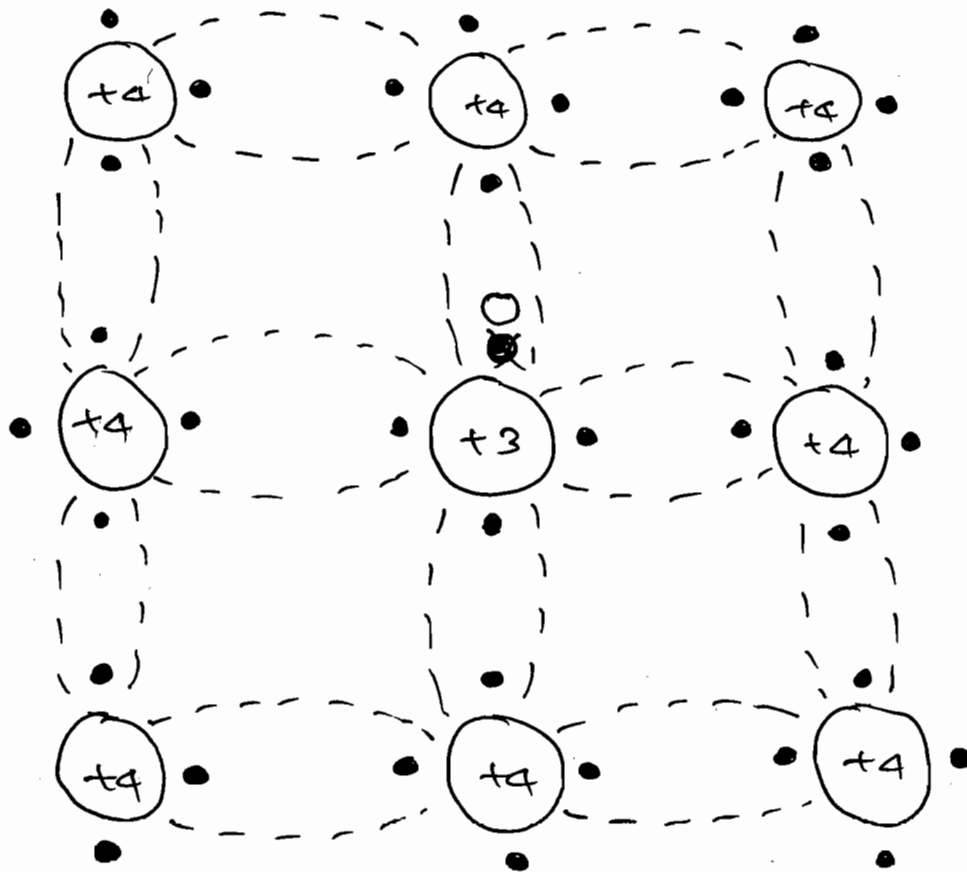


FIG - 5

⇒

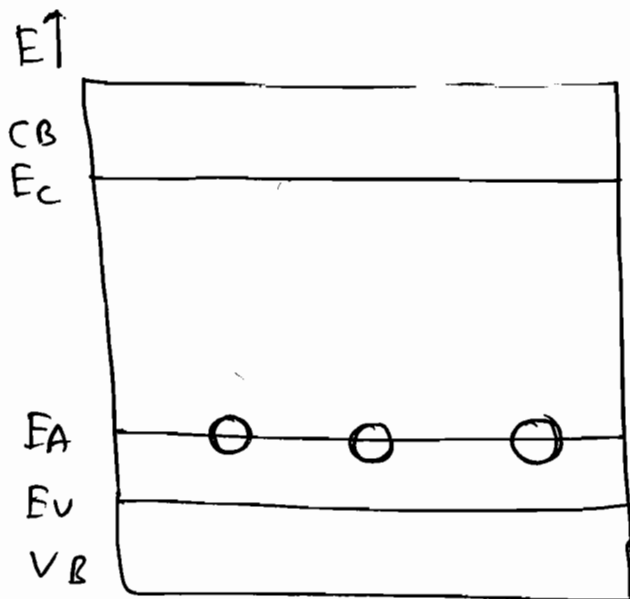


FIG - 6

⇒ At 0°K from fig-7 $n=0$ & $p=0$. Hence
 $\sigma=0$, $R=\infty$ & $I=0$. i.e. Insulator.

⇒ At 50°K for Ge (0.7eV) 100°K for Si
 electrons gain energy and move to
 holes at E_A level than all the

⇒

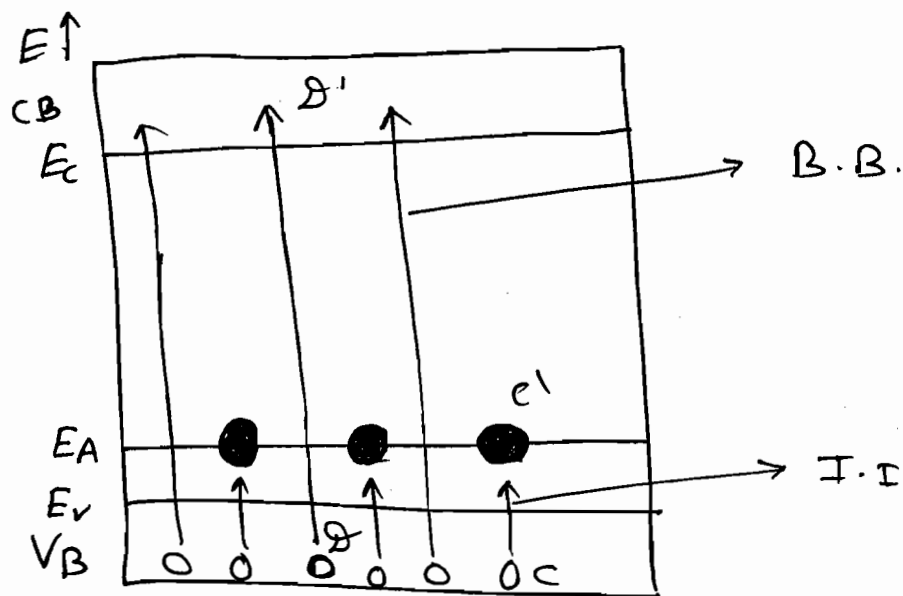


FIG- (8)

holes at E_A level disappears and equal no. of holes get created in valance Band. Hence, $n=0$ & $p>0$. Hence $\sigma>0$
 $R<\infty$ & $I>0$. i.e. Conductor.

⇒ Trivalent impurity by accepting electron becomes negative ion called impurity ionization (I.I). Trivalent atom by accepting e^- creates hole and supports current hence called acceptor atom.

→ E_A : Accceptor Energy Level.

⇒ At 300K EHP Generation (or) Band to Band (B.B) transition occurs. Hence n increases and p increases hence σ increases R decreases and I increases.

⇒

Majority	Carriers	→	hole
minority	Carriers	→	e^-
majority	currents	→	I_p
minority	currents	→	I_n



Note:

→ At very high temp. all extrinsic

✓✓ Semiconductors become intrinsic because

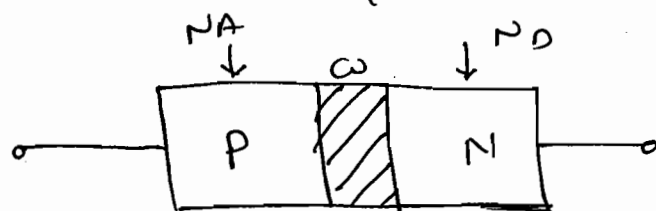
band to band transition dominates
(or) over through impurities ionization

and at this temp. usefulness of all electronic devices will get terminated.

⇒ n-Type:

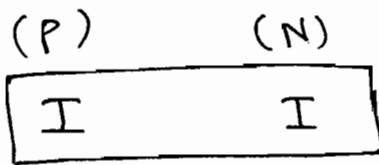
	e^- (I.I)	e^- (B.B)	hole (B.B)	
300°K:	10^2	10^2	10^2	: $n \neq p \Rightarrow \text{EXT.}$
400°K:	10^2	10^3	10^3	: $n \neq p \Rightarrow \text{EXT.}$
700°K:	10^2	10^5	10^5	: $n \approx p \Rightarrow \text{INT.}$

⇒



300°K: FB: + - : $w \downarrow \rightarrow I_T : ON$
RB: - + : $w \uparrow \rightarrow I_T : OFF$

⇒ 700k



~~Switch~~

FB: + - : $\overrightarrow{I_A}$

RB: - + : $\overleftarrow{I_A}$



⇒ 300k:

n	p	n
---	---	---

 : Amplifier.

700k:

I	I	I
---	---	---

 : Attenuator.

* Mass Action Law:

⇒ The product of free electron and hole concentration in an intrinsic (or) Extrinsic Semiconductor at a given temp. is a constant given by

$$\boxed{n_p = n_i^2} \quad \text{--- (1)}$$

Where; n_i : intrinsic concentration given

by

$$\boxed{n_i^2 = A_0 T^3 e^{-E_{go}/KT}} \quad \text{--- (2)}$$

where A_0 is a constant dependent on

Semiconductor and independent on temp.

T : Temp in $^{\circ}\text{K}$.

E_{co} : Energy Band gap at 0°K .

k : Boltzman Constant in $\text{eV}/^{\circ}\text{K}$.

$$\Rightarrow \boxed{300^{\circ}\text{K}} : \text{INT} : n_p = n_i^2$$
$$\downarrow$$
$$\text{N-type} : (n) (p) = n_i^2$$

$\Rightarrow$ Consider an Intrinsic Semiconductor at 300°K with $n \cdot p = n_i^2$ say it is converted to n-type without changing temperature then n_i^2 is constant. Due to donor e^- concentration n increases hence prob. of hole recombine with electron increases. Increase to n and decrease to p counter make $n \cdot p = n_i^2$ constant.

$$\Rightarrow \boxed{\text{INT}} :$$
$$300^{\circ}\text{K} : n_1 p_1 = n_{i1}^2$$
$$400^{\circ}\text{K} : n_2 p_2 = n_{i2}^2$$

$\Rightarrow$ Consider an intrinsic semiconductor at 300°K with $n_1 \cdot p_1 = n_{i1}^2$ say temp.

increases to 400 K and n_{i1}^2 to n_{i2}^2 .

Due to increase in temp. EHP generation increases hence n_1, p_1 increases to n_2, p_2 such that $n_2 \cdot p_2 = n_{i2}^2$.

$\Rightarrow n \cdot p = n_i^2$ is valid at a given temp.

It temp changes again valid but for different value. i.e.

$$\Rightarrow \boxed{n_1 \cdot p_1 \neq n_2 \cdot p_2}$$
$$\Rightarrow \boxed{n_{i1}^2 \neq n_{i2}^2}$$

$\Rightarrow$ Based on electrical neutrality

$$\boxed{N_D + p = N_A + n} \quad \text{--- (3)}$$

$\Rightarrow$ LHS gives total +ve ~~ions~~^{charges} per cubic volume given by donor ions and holes.

$\Rightarrow$ RHS gives total -ve charges per cubic volume given by acceptor ions and electrons.

* Case - I :- Intrinsic ($N_D = N_A = 0$).

$$\Rightarrow \cancel{N_D} + p = \cancel{N_A} + n.$$

$$\Rightarrow \boxed{n = p} \quad \text{--- (4)}$$

From e_n^n ① & ④

$$\boxed{n = p = n_i} \text{ ————— ⑤}$$

Case - II : N - Type ($N_D > 0$, $N_A = 0$)

$\Rightarrow$ From e_n^n - ③

$$N_D + \cancel{p_n} = \cancel{N_A} + n_n$$

Neglect

When, p_n , n_n is hole, free electron
Concentration in N-Type.

$\rightarrow$

~~$N_D + p_n = N_A + n_n$~~

$$\boxed{n_n \approx N_D} \text{ ————— ⑥}$$

Note: $n \cdot p = n_i^2$ is valid for only one Semiconductor which can be Intrinsic (or) n-type (or) p-type. It is not applicable across multiple Semiconductors.

$$\rightarrow n_n p_n = n_i^2$$

$$\rightarrow \boxed{p_n = \frac{n_i^2}{n_n} \approx \frac{n_i^2}{N_D}} \text{ ————— ⑦}$$

Case- III : P-Type ($N_D = 0$, $N_A > 0$).

$$\Rightarrow \cancel{N_D} + P_p = N_A + \cancel{n_p} \quad \text{neglect.}$$

$$\Rightarrow \boxed{P_p \approx N_A} \quad \text{--- (8)}$$

$$\rightarrow n_p P_p = n_i^2$$

$$\therefore \boxed{n_p = \frac{n_i^2}{P_p} = \frac{n_i^2}{N_A}} \quad \text{--- (9)}$$

* Diffusion

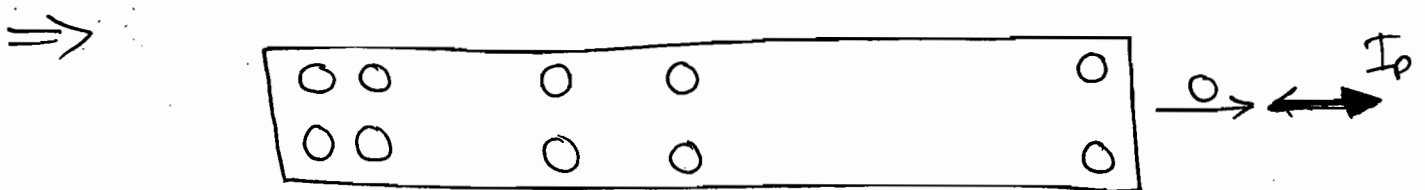


Fig-1

$\Rightarrow$ Consider a p-type semiconductor as in Fig-1. Due to difference in concentration, holes diffuse from higher to lower (left to right). Concentrated area until uniform carrier concentration ($\frac{dp}{dx} = 0$) is achieved and produced hole diffusion current I_p where hole diffusion

Current density $J_p(x)$ is given by

$$J_p(x) = \frac{I_p}{A} = -qD_p \frac{dp}{dx}$$

$\Rightarrow$

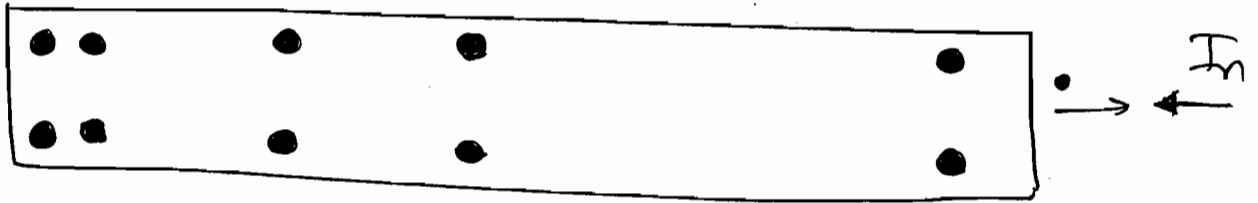


FIG-2

$\Rightarrow$ Consider an n-type Semiconductor (fig-2) with a non-zero value of concentration gradient ($\frac{dn}{dx} \neq 0$). Due to difference in concentration ^{electrons} ~~holes~~ diffuse from higher to lower (Left to right) concentrated area until uniform concentration ($\frac{dn}{dx} = 0$) is achieved and produced electron diffusion current. Where electron diffusion current density $J_n(x)$ is given by,

$$J_n(x) = \frac{I_n}{A} = +qD_n \frac{dn}{dx}$$

$\Rightarrow$ If a Charge Carrier moves due to difference in concentration it is said to be diffusing where as if a Charge Carrier moves due to attraction (or) repulsion of a voltage it is said to be drifting. Diffusion current is proportional to concentration gradient of Charge Carriers where as drift current is proportional to concentration of charge Carriers and electric field where drift current density J is given by

$$\Rightarrow J = \frac{I}{A} = \sigma E = (nq\mu_n + pq\mu_p) E.$$

$\Rightarrow D_p, D_n$: Diffusion Constants for hole, electron given by

$$\frac{D_p}{\mu_p} = \frac{D_n}{\mu_n} = V_T = \frac{kT}{q} = \frac{T^\circ K}{11,600} = 0.026V \quad (\text{AT } 300K)$$

$\nearrow$
Einstein's Relationship

$$k = eV/k$$

$$E = \sigma/k$$

$\rightarrow V_T$: thermal Voltage

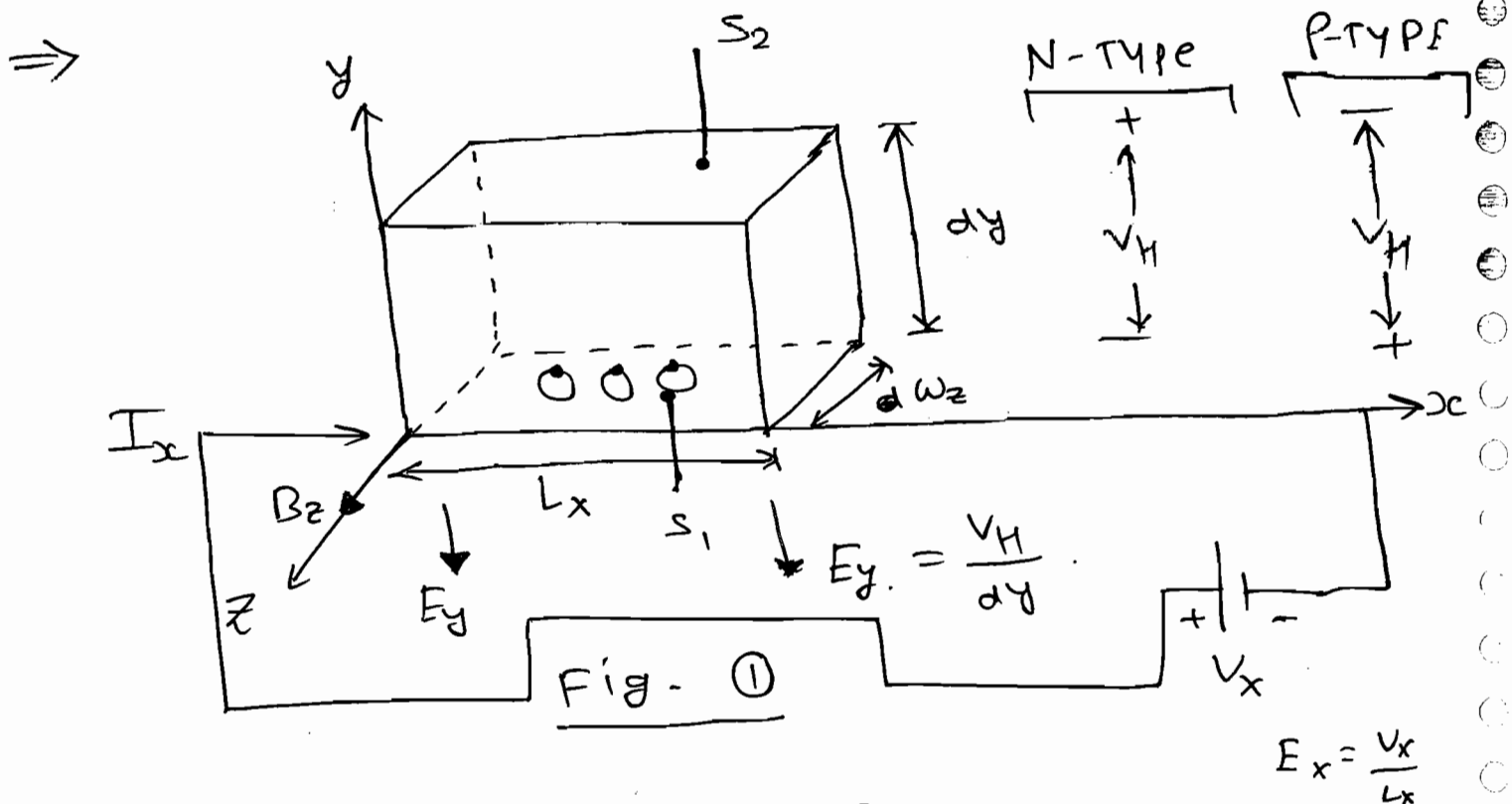
k : Boltzman's constant in $eV/^\circ K$.

$\bar{K}$ = Boltzman Constant in J/K.

T: temp. in °K.

* Hall Effect:

⇒ If a Semiconductor carrying a current I_x is placed in transverse magnetic field B_z then an electric field E_y gets induced in a direction perpendicular to I_x & B_z .



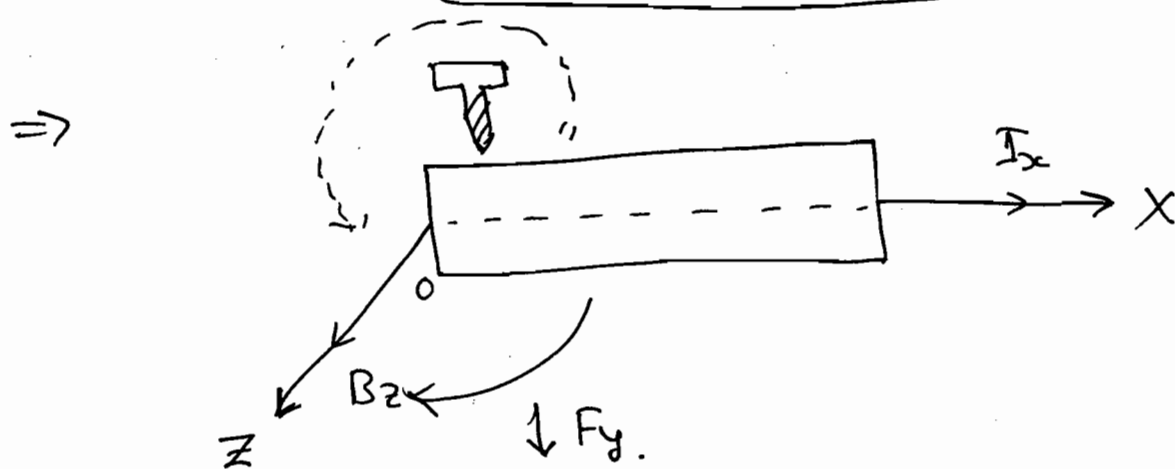
S_1, S_2 : Surface-1, Surface-2.

→ If a semiconductor carrying a current I_x is placed in a transverse magnetic field B_z then according to a motor

Law a force gets induced in a direction perpendicular to I_x & B_z in the direction of forward motion of a right handed screw around from I_x to B_z .

$$V_H = \frac{B_z \cdot I_x}{e n_z} \quad (V)$$

e = Charge density



$\Rightarrow$ Due to the induced force all the charge carriers are pulled towards a surface, hence that surface becomes negatively (or) positively charged w.r.t. other surface. Hence, the potential (or) voltage called Hall voltage V_H gets induced along y-dimension of sample. Hence an electric field E_y gets induced along y-direction. It was proved in 1879 by Edwin Hall.

* Applications:

⇒ ① It can be used to find the type of semiconductor. (N or P type) by looking at V_H polarities.

⇒ ② It can be used to find charge density and hence carrier concentration (electron (or) Hole concentration).

$$\checkmark V_H = \frac{\checkmark B_z \cdot \checkmark I_x}{\checkmark e \cdot \checkmark w_z} \rightarrow \checkmark$$

N-Type : $\checkmark e_n = \checkmark n \checkmark \rightarrow \checkmark n = \checkmark$

P-Type : $\checkmark e_p = \checkmark p \checkmark \rightarrow \checkmark p = \checkmark$

⇒ ③ Given mobility, conductivity can be calculate (or) viceversa.

⇒ Hall constant (or) Hall coefficient

$$\boxed{R_H = \frac{1}{e} = \frac{\checkmark V_H \cdot \checkmark w_z}{\checkmark B_z \cdot \checkmark I_x} \text{ m}^3/\text{C} \rightarrow R_H = \checkmark}$$

$$\rightarrow \sigma = \frac{1}{\rho} \rightarrow \mu = \frac{\sigma}{e}$$

σ : conductivity

e : charge density

μ : mobility.

$$\Rightarrow \boxed{\mu = \frac{1}{e} R_H}$$

②

$\Rightarrow$ It can be used to multiply two signals. (Hall effect multiplier).

Q Calculate μ_p for a p-type Germanium bar connected as in figure - 1 and is exhibiting Hall effect given

$$B_z = 0.1 \text{ Wb/m}^2$$

$$dy = wz = 3 \text{ mm.}$$

$$V_H = 50 \text{ mV.}$$

$$I_x = 10 \mu\text{A.}$$

$$\rho = 200,000 \Omega\text{-cm.}$$

Soln:

$$R_H = \frac{V_H \cdot wz}{B_z \cdot I_x}$$

$$\therefore R_H = \frac{50 \times 10^{-3} \times 3 \times 10^{-3}}{0.1 \times 10 \times 10^{-6}}$$

$$\therefore R_H = 150 \Omega \cdot \text{cm}^2 / \text{C.}$$

$$\therefore \mu = \sigma \cdot R_H.$$

$$\therefore \mu = \frac{1}{\rho} \cdot R_H.$$

$\rho \rightarrow \text{resistivity.}$

$$\therefore \mu = \frac{1}{2 \times 10^3} \times 150.$$

$$\therefore \mu = 75 \times 10^{-3} \text{ m}^2/\text{V-s.}$$

Note: In $R_H = \frac{1}{p} \frac{e a^n}{s}$ s is charge density where a & p given in problem statement is Resistivity.

Q Find the magnitude of Hall Voltage V_H in an N-Type Ge bar connected as in fig-① and is exhibiting Hall effect given.

$$N_0 = 10^{17} \text{ cm}^{-3}$$

$$B_z = 0.1 \text{ Wb/m}^2$$

$$dy = 3 \text{ mm}$$

$$E_x = 5 \text{ V/cm}$$

$$\mu_n = 3800 \text{ cm}^2/\text{V-sec}$$

Soln:

$$V_H = \frac{B_z \cdot I_x}{e \cdot n \cdot A}$$

Note: E_x , V_x , I_x , B_z are applied quantities
 F_y , V_H & E_y are induced quantities.

$$J_x = \frac{I_x}{A}$$

Note In drift and diffusion current density $e a^n$, ($J = I/A$) cross sectional area A is defined as perpendicular area for current.

$$\rightarrow \boxed{J_x = \frac{I_x}{w_z \cdot dy} = S \cdot v_d = S \mu_n E_x} \quad \checkmark$$

S = charge density.

v_d = drift velocity.

$\rightarrow \mu$: mobility

E : electric field.

$$\boxed{\frac{I_x}{w_z} = S \mu_n E_x dy} \quad \checkmark \quad \text{--- (2)}$$

Sub. eq (2) into (1).

$$V_H = \frac{B_z}{e} \cdot e \mu_n E_x dy.$$

$$\therefore \boxed{V_H = B_z \cdot \mu_n \cdot E_x \cdot dy} \quad \checkmark$$

$$\therefore V_H = 0.1 \times 3800 \times 10^{-4} \times 5 \times 10^2 \times 3 \times 10^{-3}.$$

$$\therefore V_H = 5700 \times 10^{-5}$$

$$\therefore \boxed{V_H = 57 \text{ mV.}}$$

Q A p-type silicon specimen is exhibiting Hall effect and is connected as in fig-1. Calculate induced voltage given

$$B_z = 0.1 \text{ wb/m}^2.$$

$$E_y = 750 \text{ V/m.}$$

$$dy = 0.009 \text{ m.}$$

Soln:

$$V_H = E_y \cdot dy$$

$$= 750 \times 0.009$$

$$\therefore V_H = 6.75V$$